



# **Compact Linear Collider Beam Instrumentation**

T. Lefevre, CERN for the CLIC BI team

- CLIC beam instrumentation requirements
- Status on Linear Collider beam instrumentation
- Status and plans for the coming years









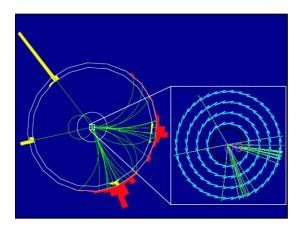
### Collider luminosity [cm<sup>-2</sup>s<sup>-1</sup>] is approximately given by

$$L = \frac{n_b N^2 f_{rep}}{4\pi \sigma_x^* \sigma_y^*} \times H_D$$

- $n_b$  = bunches / train
- N = particles per bunch
- $f_{rep}$  = repetition frequency
- $\sigma_{x,y}$  = beam size at IP
- $H_D$  = beam-beam enhancement factor

## A linear collider uses the beam pulses only once:

- Need to accelerate lots of particles
- Need very small beam sizes





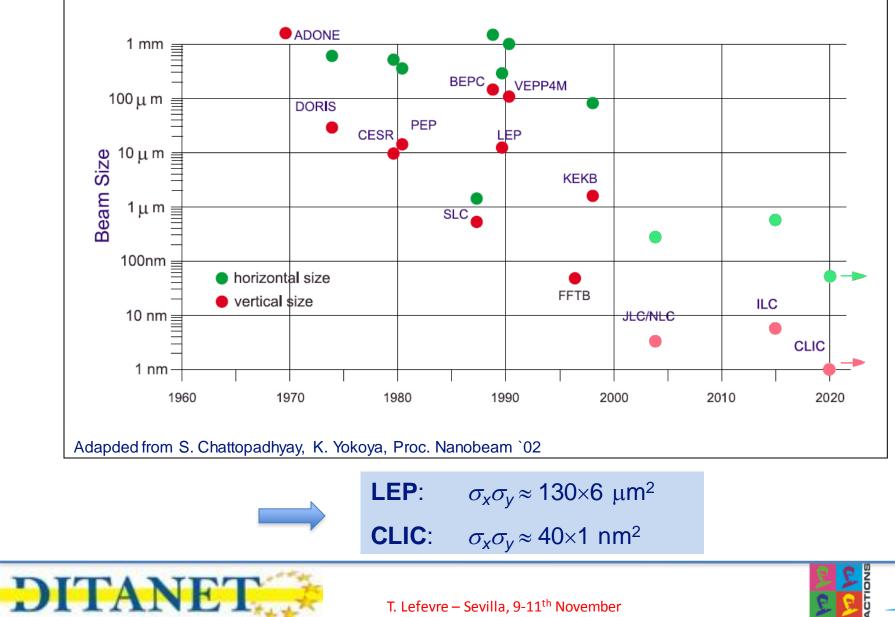
## The small beam size challenge



۵

ARIE CURIE

PEOPLE



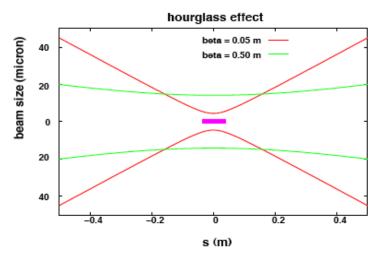


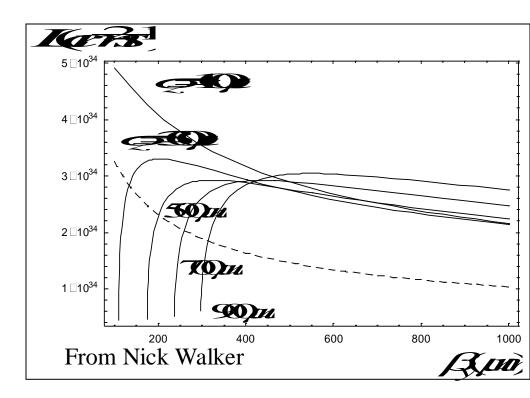




For achieving small beam size at IP, the beta function rapidly increases as the particle move away from the collision point

#### Variation of beam size along the bunch





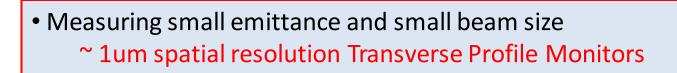
Rule:

'Keep  $\beta_v \sim \sigma_z'$  **45um for CLIC** 









- Measuring Short bunch length
  - ~ 20fs time resolution Longitudinal Profile Monitors
- Conservation of emittance over long distances relies on precise alignment high accuracy (5um) high resolution (50nm) Beam Position Monitor
- Dump the beam safely and properly

Dealing with high beam power (tens of MW)

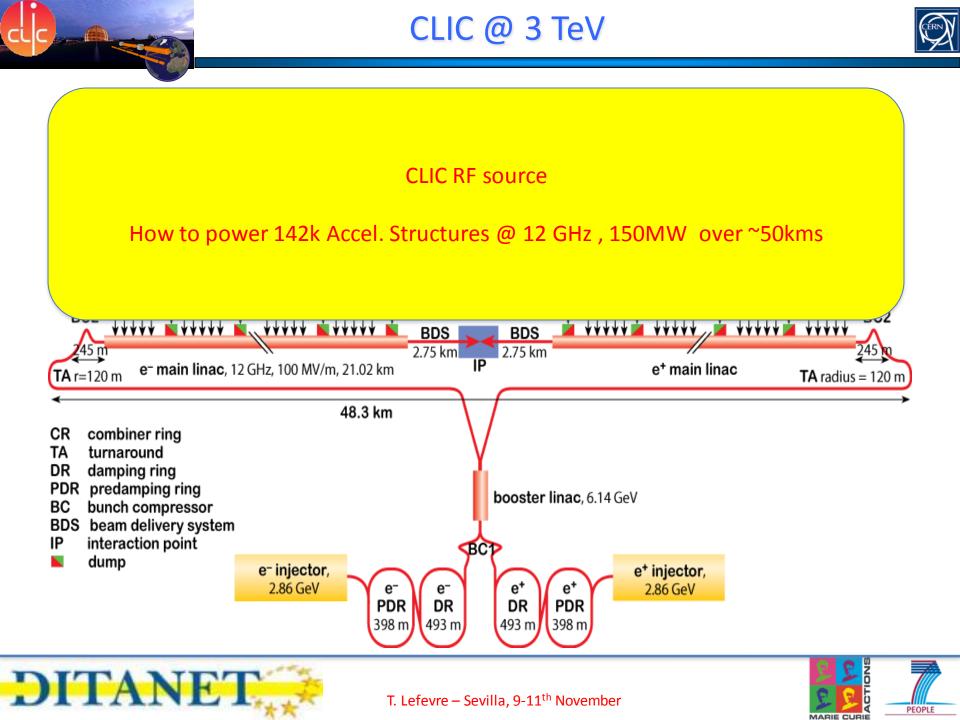
<del>LIECTI OTI GUIT</del>

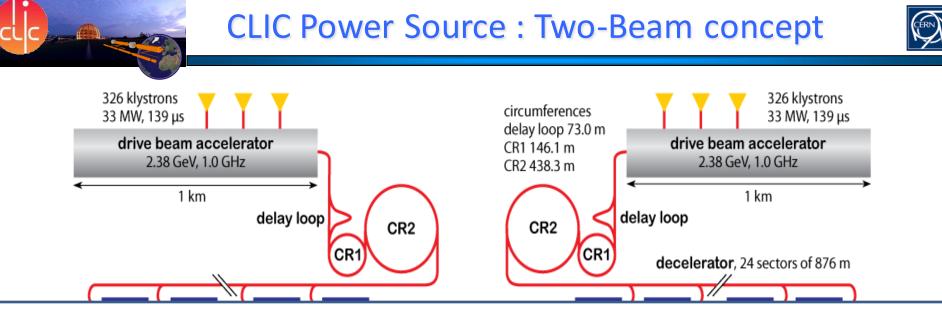
Deliver stable beam current

Use electrons to pairproduce positrons









• Acceleration (94% RF to be efficiency) using fully loaded accelerating structures : **see the talk by Maja Olvegard later today** 

• Innovative Bunch Multiplication Frequency scheme: see Poster by Mathilde Favier

• Manipulating high charge beams (Machine Protection issues, Radiation level, Non intercepting beam diagnostic, ..) : **see poster by Sophie Mallows** 

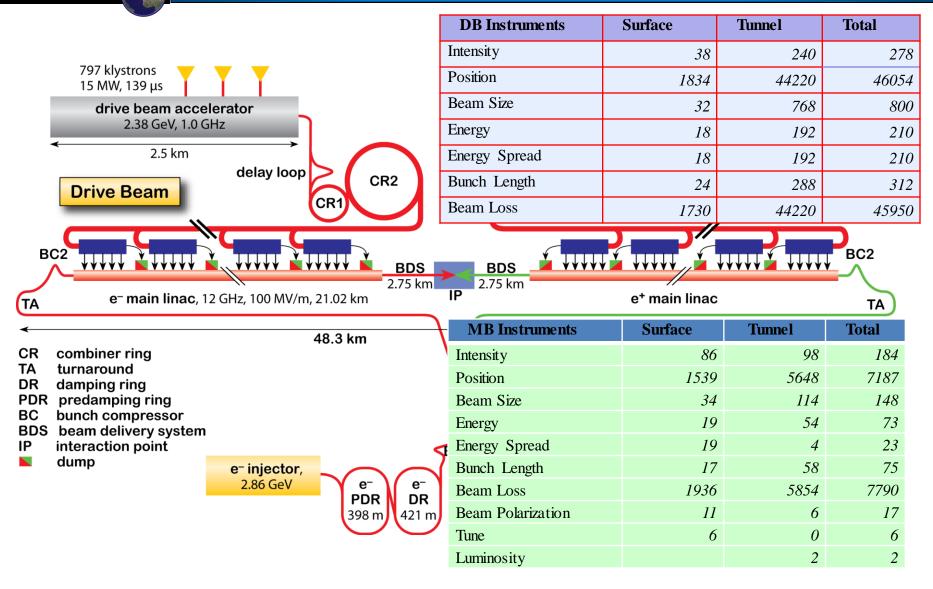
• In addition, there are very strict tolerances/requirements on the beam phase stability (0.1º@12GHz)

• Reliability and availability : This is 'just' the RF Source !



## **CLIC Instrumentation in Numbers**









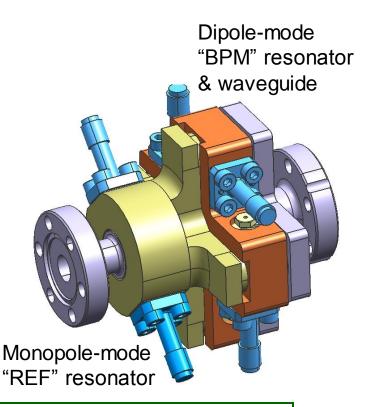


DITANET



## Dispersive emittance dilutions along the main linac due to offset of quadrupoles

- Beam based alignment to define a precise reference using ~4200 high resolution (50nm) cavity BPM
- Quadrupoles on movers and stabilized in position using actuators and active feedback system



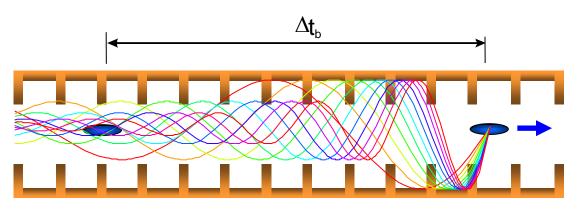
- WG-loaded, low-Q X-Band design (Fermilab-CERN)
  - $Q_l \approx 260$ , resonator material: 304 stainless steel
  - ~50 nsec time resolution, <50 nm spatial resolution</li>
- First prototype under fabrication Test with beam next year on CTF3
- Talk by Nirav Joshi (RHUL) on Wednesday







Wakefields in accelerating structures (damping of high order modes)



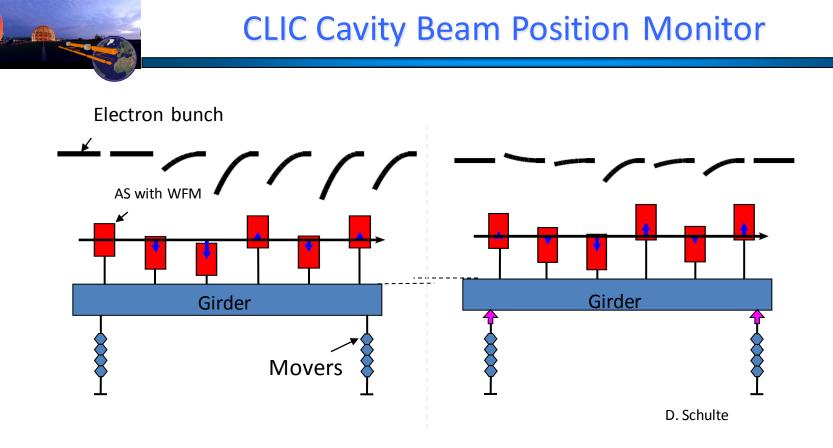


Bunches passing through an accelerating structure off-centre excite high order modes which perturbs later bunches

- Tolerances for acc. Structures alignment
- Cavity alignment at the 300  $\mu m$  level 5  $\mu m$
- Need wakefield monitor to measure the relative position of a cavity with respect to the beam



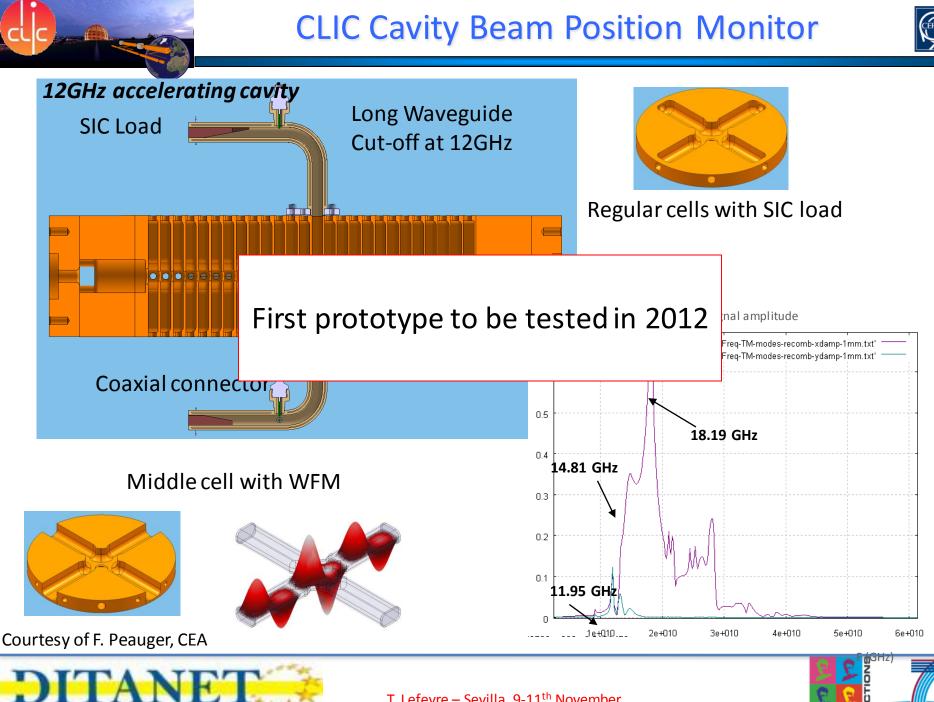




- > Wakefield kicks from misaligned AS can be cancelled by another AS
- One WFM per structure (142k monitors) and mean offset of the 8 AS computed
- ➢ WFM is a cavity BPM with 5um resolution
- > Need to get rid of the 100MW of RF power at 12GHz present in the structures







T. Lefevre – Sevilla, 9-11<sup>th</sup> November

PEOPLE

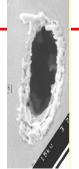




- Critical Issue on micron resolution beam profile measurements (> 100 monitors)
- Charge density limitation problems in many places / Strong need for non-interceptive

devices : two systems required to cover the total dynamic range





Combine Optical Transition screens and Laser Wire Scanners

- OTR used almost everywhere for commissioning (and more)
- LWS 1um resolution required for the Main beam
- LWS used in the Drive Beam injector complex for high charge beams (full charge)

## Talk on LWS by T. Aumeyr this afternoon

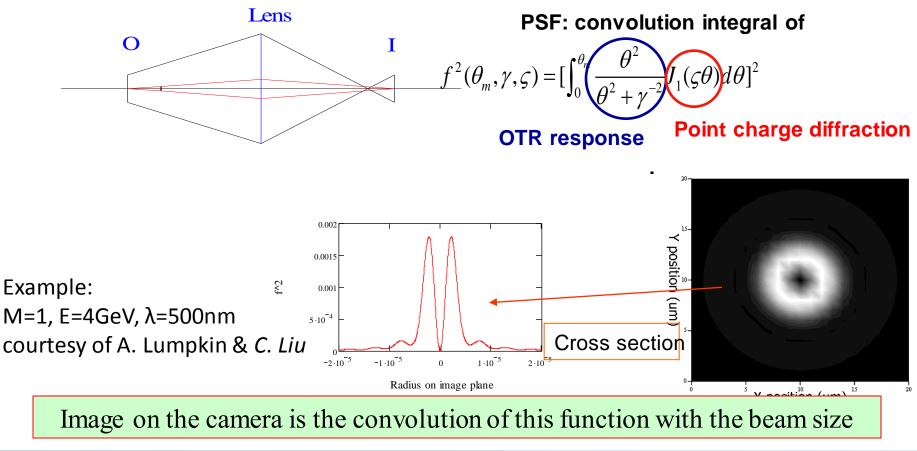








At the diffraction limit (beam size  $\sim \lambda/\Delta\theta$  with  $\Delta\theta$  the angular acceptance of the optical system), the image of a point source (radiating a ring pattern) is defined by the OTR point spread function (PSF):







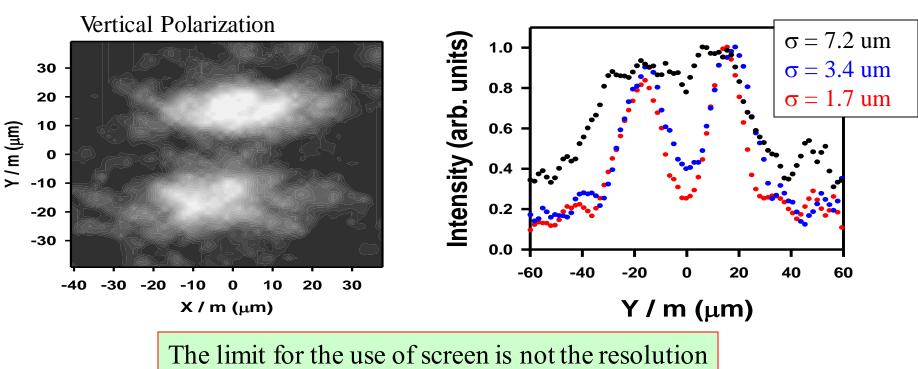




### Measurements performed on ATF2 @ KEK

Courtesy of P. Karataev





but the thermal resistance of the screen

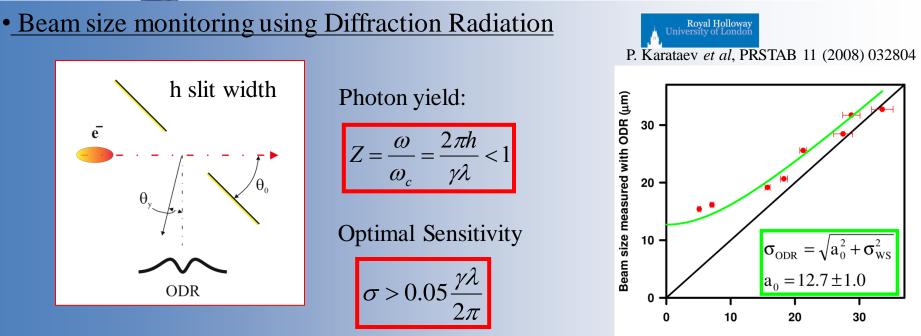
Similar system by Ake Andersson (maxlab) using the vertical polarization of Synchrotron radiation





Non-interceptive beam size monitors using DR





Beam size measured with wire scanner ( $\mu$ m)

• Already few existing prototypes in IR and visible range E. Chiadroni et al, PAC 2007 pp3982 and A.H. Lumpkin *et al*, *PRST-AB* **10** (2007) 022802

- Alternative technology for both Drive and Main Beams
  - Drive Beam Injector Complex (2.4GeV) typical beam size of 50-100um
  - Ring To Main Linac (RTML) complex (2-9GeV) Typical beam size of 5-10um
  - >100 of devices in total
  - Push the resolution to the micron range using DR in extreme UV
  - Experimental validation foreseen on CESRTA @ Cornell first stage (10um resolution in 2012)





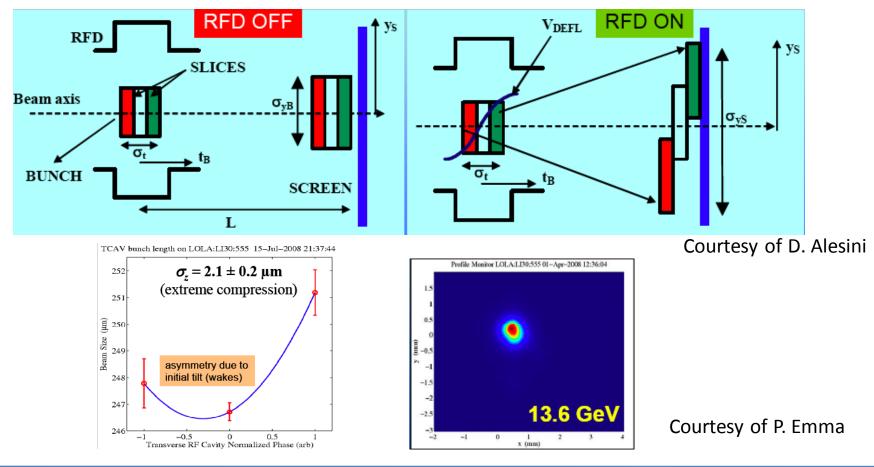




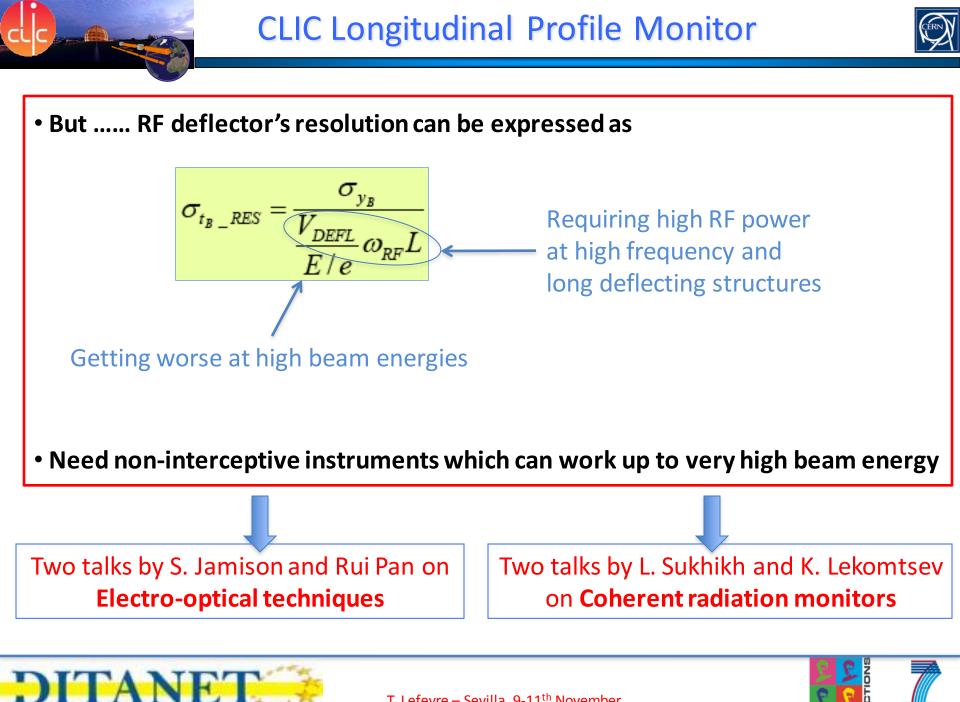
Critical Issue on 20fs resolution bunch profile monitor

DITANE

• Resolution already obtained by radio-frequency deflecting cavity ...











- R&D on Critical issues known since long time already...
  50nm precision BPM 20fs precision bunch length monitor 1um transverse profile monitor
- Conceptual Design Report
  - Collect requirements for the whole CLIC complex (started in 2008)
    - 200kms of beam line, more than 10<sup>5</sup> instruments
  - Defined Baseline CLIC instrumentation with appropriate technology choice
  - Propose Alternative solutions which would impact either on cost or performance



BI Chapter is completed (waiting for publication) ! Many Thanks to the all of the 26 co-authors, mainly from collaborating institutes









- CLIC goes in the Project Preparation Phase (2012-16)
  - Testing of CLIC prototypes
  - Integration of CLIC instruments in the machine layout
  - Operational issues: reliability study and maintenance strategy
  - Cost optimization
    - Simplicity if applicable (not always compatible with tight tolerances)
    - Standardization (detectors, electronics) is a key concept
    - Gain in Mass production ?



